

# FIRST RESULTS FROM Nb<sub>3</sub>Sn COATINGS OF 2.6 GHz Nb SRF CAVITIES USING DC CYLINDRICAL MAGNETRON SPUTTERING SYSTEM

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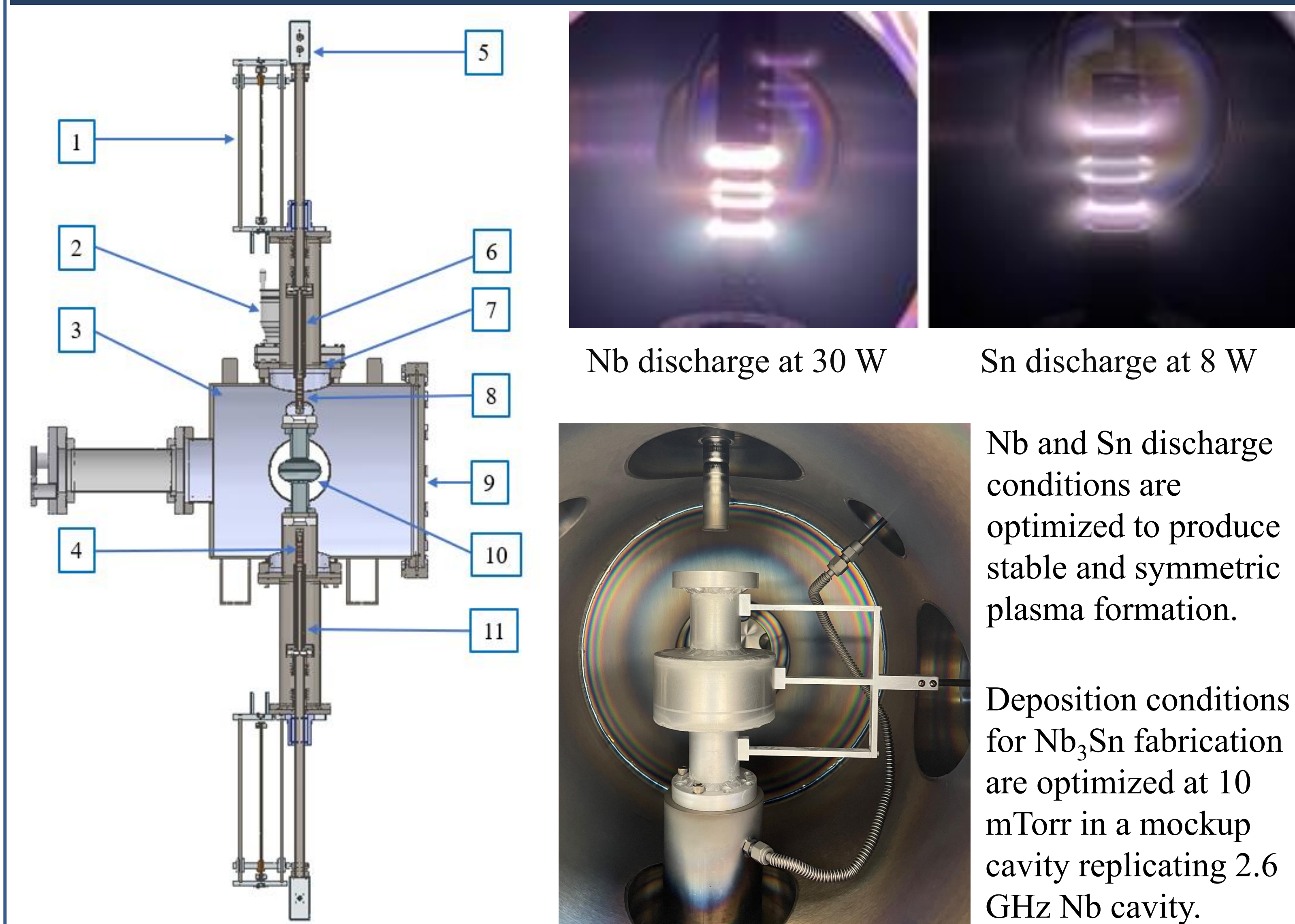
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## Abstract

Nb<sub>3</sub>Sn is considered as the next generation material to replace Nb for SRF cavity. A DC cylindrical magnetron sputtering system is designed and commissioned to coat Nb<sub>3</sub>Sn into SRF cavity. After optimizing the deposition conditions in mockup cavity, using multilayer sequential sputtering of Nb and Sn followed by annealing at 950 °C for 3 hours, Nb<sub>3</sub>Sn films are fabricated on flat substrates. Later, three 2.6 GHz Nb cavities are coated with ~1 μm Nb<sub>3</sub>Sn film and the coated cavities showed superconducting transition between 17.9 – 18 K. One of the Nb<sub>3</sub>Sn coated cavities demonstrated Q<sub>0</sub> of 3.2 × 10<sup>8</sup> at 4.4 K and Q<sub>0</sub> of 1.1 × 10<sup>9</sup> at 2.0 K, both at E<sub>acc</sub> = 5 MV/m. The operation of the cylindrical sputtering system and results from Nb<sub>3</sub>Sn fabrication by cylindrical magnetron sputtering system on flat samples and into Nb cavities are presented.

## Operation of cylindrical magnetron sputter coater



Nb discharge at 30 W

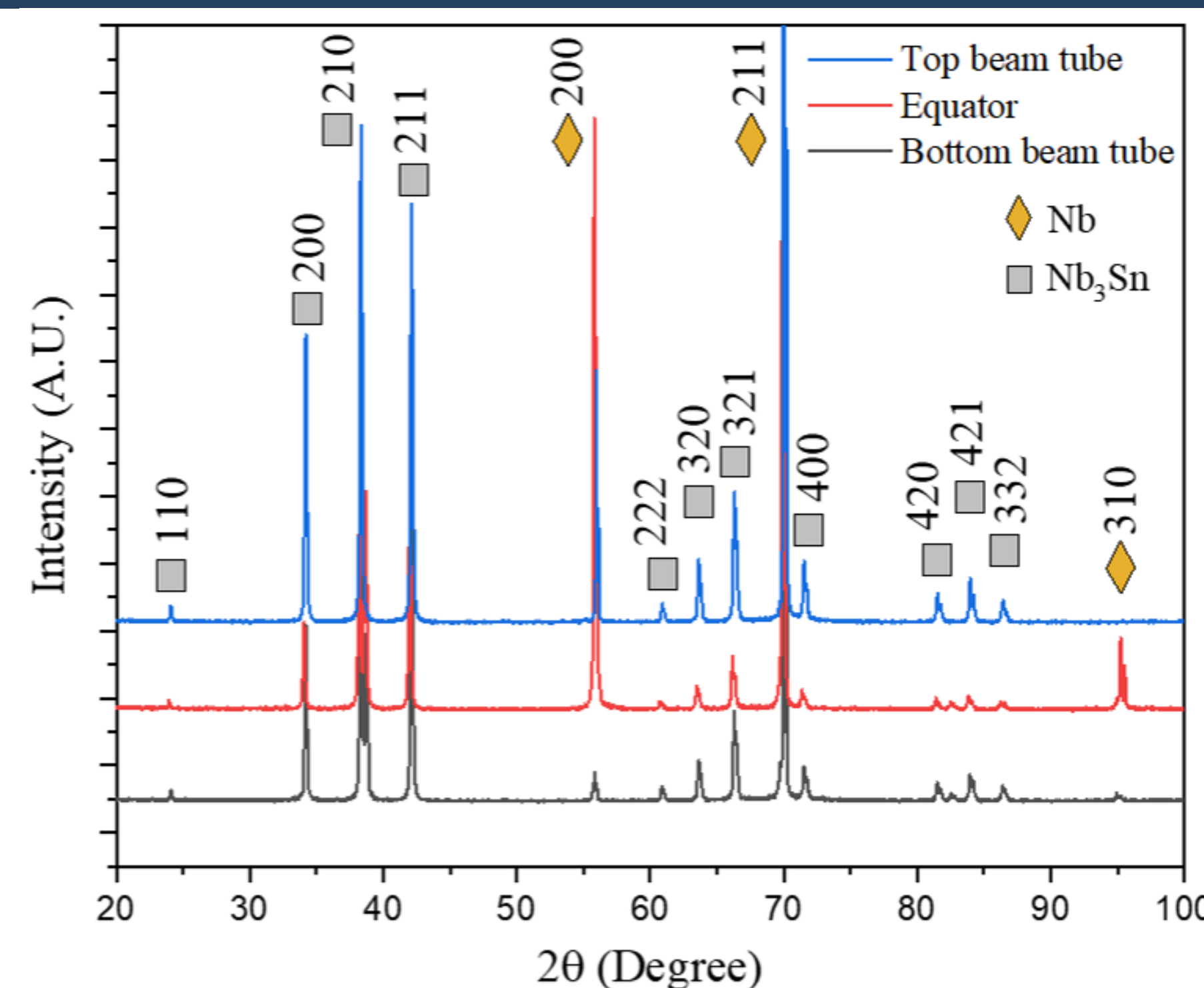
Sn discharge at 8 W

Nb and Sn discharge conditions are optimized to produce stable and symmetric plasma formation.

Deposition conditions for Nb<sub>3</sub>Sn fabrication are optimized at 10 mTorr in a mockup cavity replicating 2.6 GHz Nb cavity.

Sketch of the cylindrical magnetron sputtering system (1) Magnetron movement controller shaft, (2) Gate valve, (3) Vacuum chamber, (4) Magnets, (5) Water flow controller, (6) Top magnetron, (7) 8" ConFlat port of top magnetron, (8) Tube target, (9) Chamber door, (10) 2.6 GHz Nb SRF cavity, (11) Bottom magnetron. The magnetrons were made by Plasmionique to fit an ODU custom chamber.

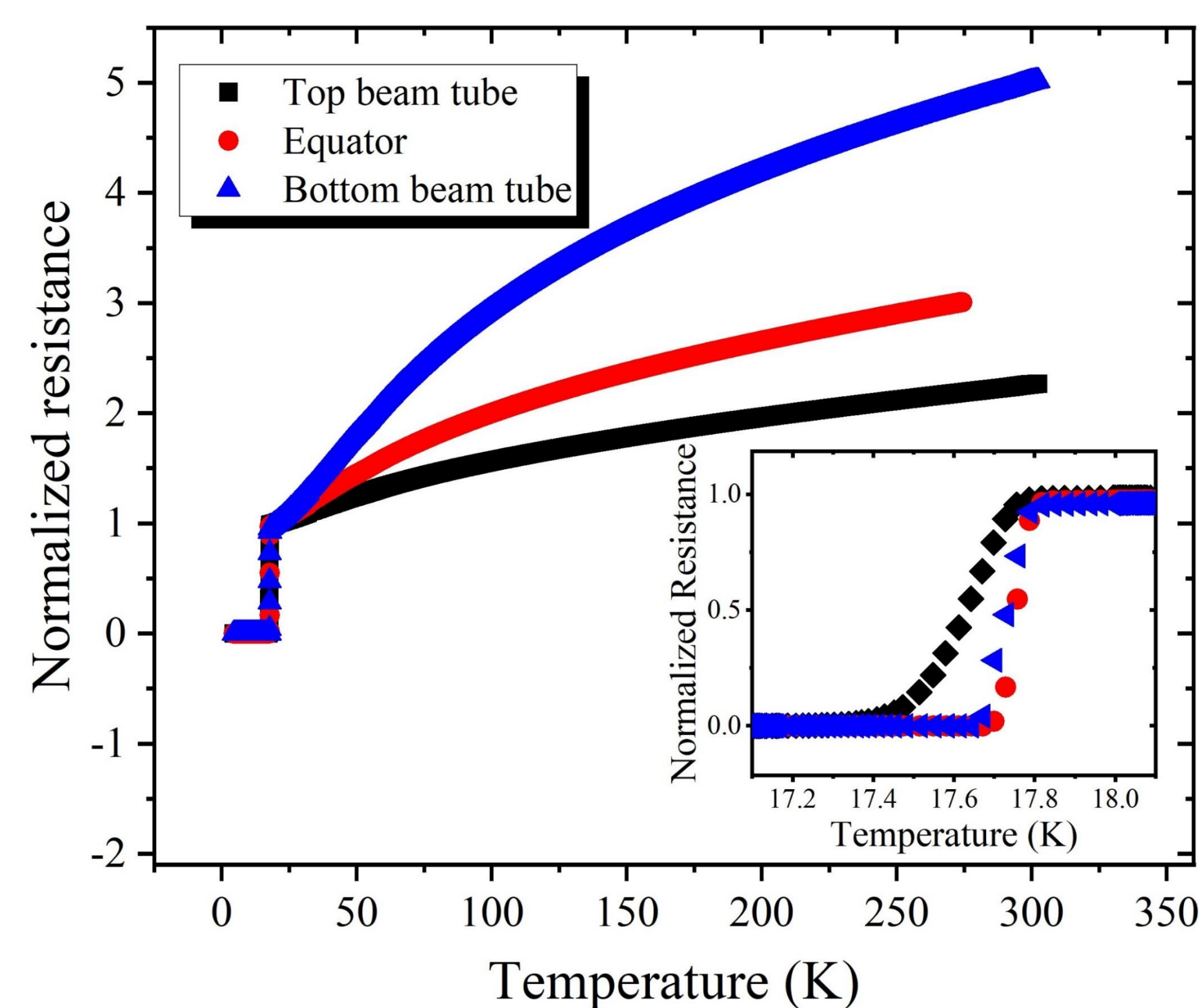
## Nb<sub>3</sub>Sn on flat Nb substrate



XRD pattern of annealed samples on Nb substrate at 950 °C for 3 h; Diffraction peaks are observed only for Nb<sub>3</sub>Sn. Nb peaks are coming from substrate.

Positions	Sn (at.%) of As-deposited films	Sn (at.%) of Annealed films
Top beam tube	33	22
Equator	32	19
Bottom beam tube	25	19

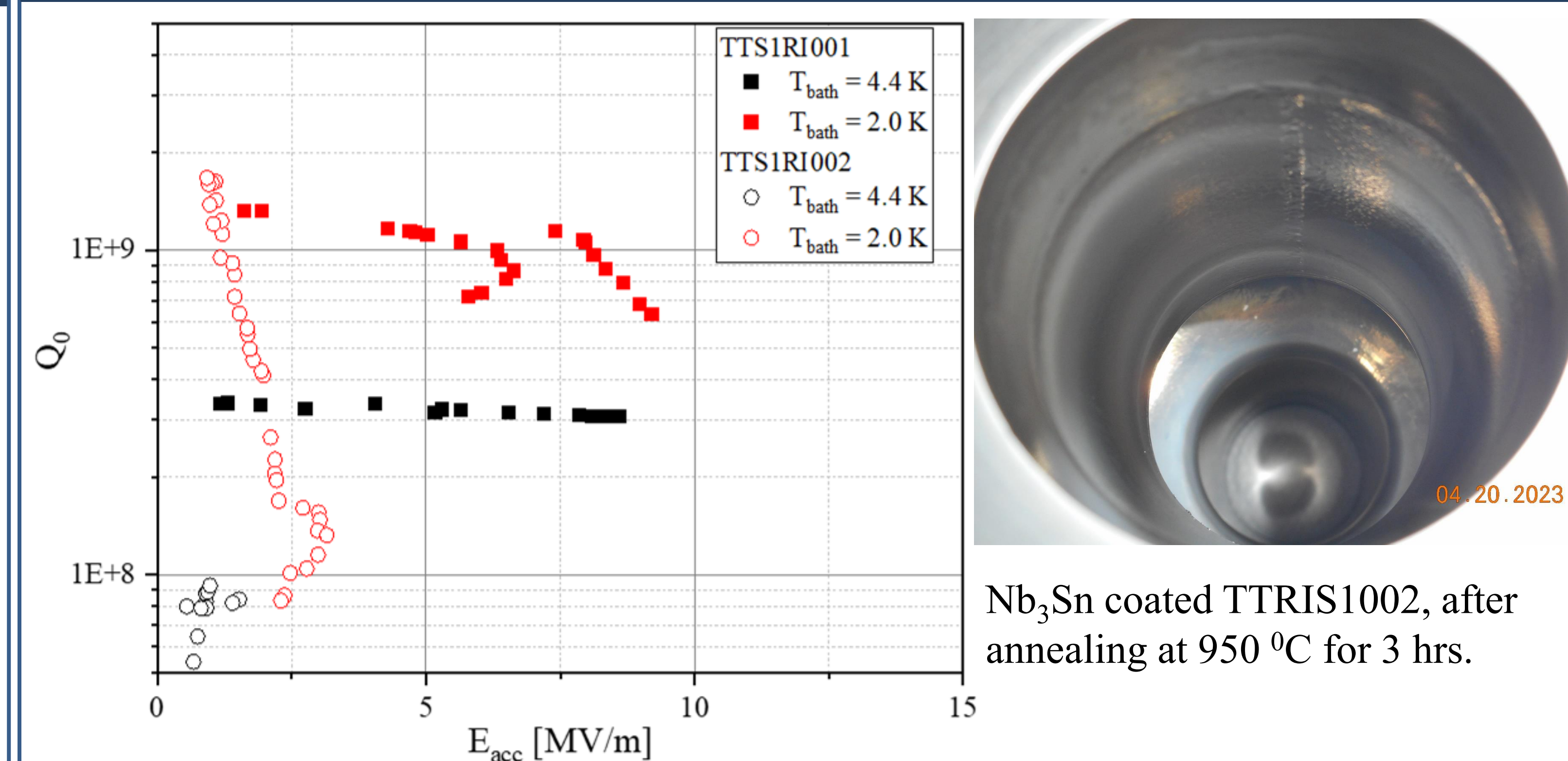
Sn atm. composition in as-deposited and annealed samples.



Sample resistance with temperature down to 4 K.

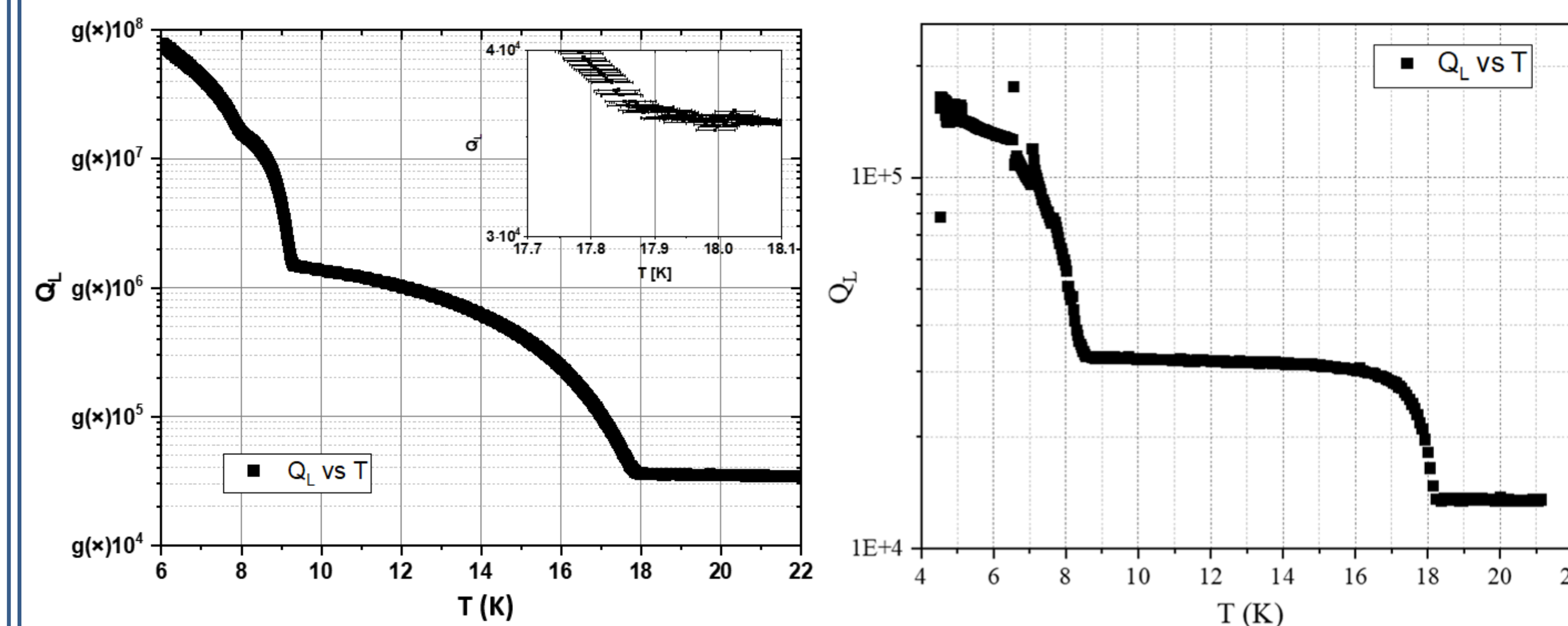
Position	T <sub>c</sub> (K)	ΔT <sub>c</sub> (K)	RRR
Top beam tube	17.61	0.24	2.26
Equator	17.76	0.06	3.00
Bottom beam tube	17.73	0.1	5.01

## Nb<sub>3</sub>Sn coated cavity performance



TTS1R001 demonstrated Q<sub>0</sub> of 3.2 × 10<sup>8</sup> at E<sub>acc</sub> = 5 MV/m at T<sub>bath</sub> = 4.4 K and Q<sub>0</sub> of 1.1 × 10<sup>9</sup> at E<sub>acc</sub> = 5 MV/m at T<sub>bath</sub> = 2 K.

TTS1R002 demonstrated Q<sub>0</sub> of 9.3 × 10<sup>7</sup> at E<sub>acc</sub> = 1 MV/m at T<sub>bath</sub> = 4.4 K and Q<sub>0</sub> of 1 × 10<sup>9</sup> at E<sub>acc</sub> = 1 MV/m at T<sub>bath</sub> = 2 K. TTS1R002 was limited by a strong Q-slope.



QL vs T (K) of Nb<sub>3</sub>Sn coated cavity TTS1R001. Superconducting transition T<sub>c</sub> observed at ~17.9 K due to Nb<sub>3</sub>Sn. Another transition is seen at ~9.2 K.

QL vs T (K) of Nb<sub>3</sub>Sn coated cavity TTS1R002. Superconducting transition T<sub>c</sub> observed at ~18 K due to Nb<sub>3</sub>Sn. Another transition is seen below 9 K.

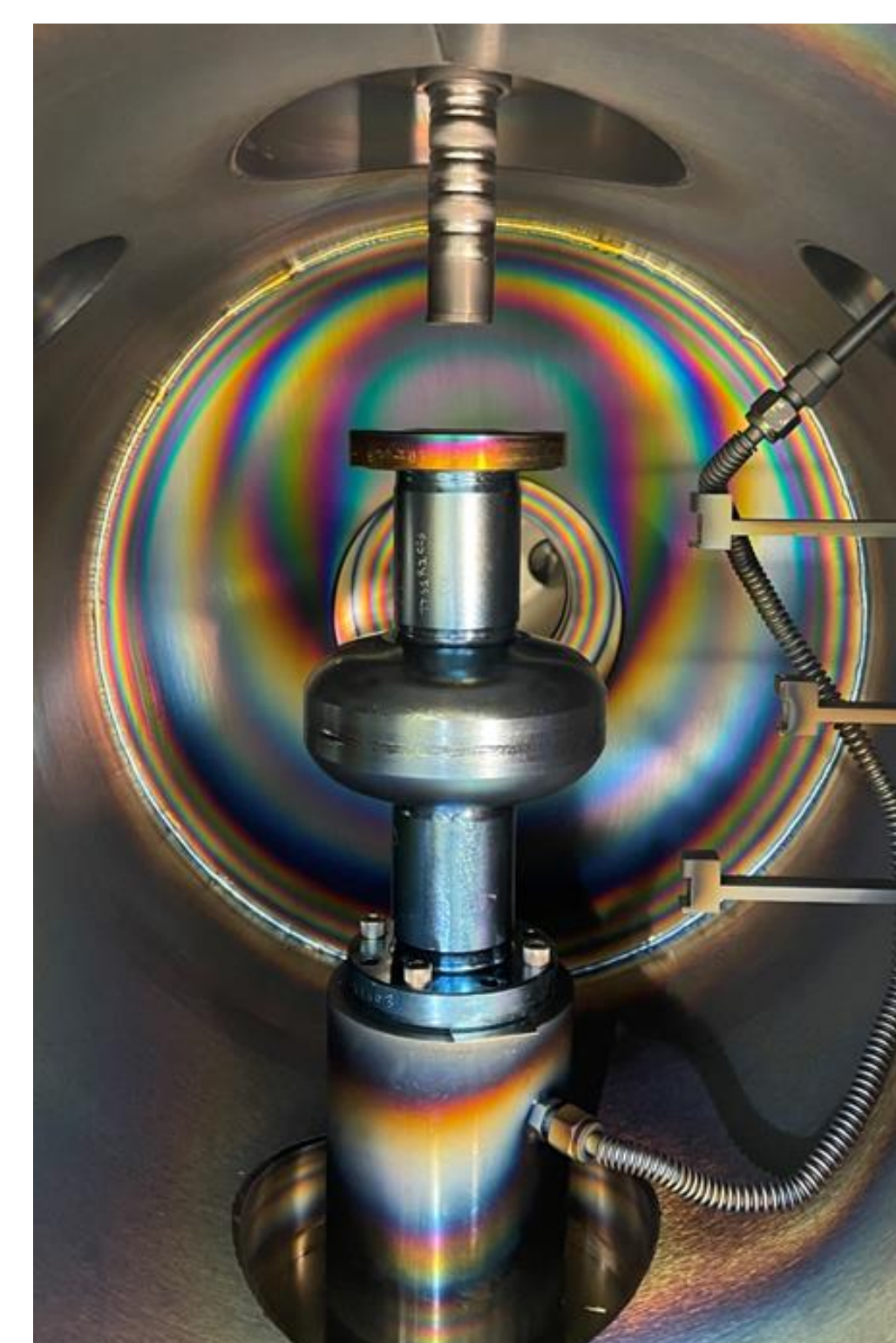
## Conclusion

Recently commissioned cylindrical magnetron sputtering system is used to coat Nb<sub>3</sub>Sn into 2.6 GHz Nb SRF cavity using multilayer sequential sputtering method. The coated cavity achieved Q<sub>0</sub> of 1.1 × 10<sup>9</sup> at 2.0 K and Q<sub>0</sub> of 3.2 × 10<sup>8</sup> at 4.4 K, both at E<sub>acc</sub> = 5 MV/m, and achieved superconducting transition temperature T<sub>c</sub> in 17.9 – 18 K range.

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## Multilayer Sequential Sputtering

Position	Total thickness of film (nm)	Layer Structure
Top beam tube	1036	46 nm Sn, 25 nm Sn, 46 nm Sn, 25 nm Sn
Equator	1008	200 nm Nb buffer layer, 46 nm Sn, 25 nm Sn
Bottom beam tube	952	Nb substrate, 46 nm Sn, 25 nm Sn



Multilayers of Nb (~46 nm) and Sn (~25 nm) are sequentially deposited for ~1 μm Nb-Sn film on Nb substrates mounted on three positions of the cavity and later annealed at 950 °C for Nb<sub>3</sub>Sn growth.

Three 2.6 GHz cavities were coated with ~1 μm Nb<sub>3</sub>Sn. 2.6 GHz Nb SRF cavity installed in the system for Nb<sub>3</sub>Sn coating.